

**BOX AF**  
**REPLY UNDER 37 C.F.R. § 1.116**  
**EXPEDITED PROCEDURE**  
**EXAMINING GROUP 2814**

PATENT  
2342-0107P

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: Mitsuhiko HIRANO                      Conf.: 3165  
Appl. No.: 08/813,200                              Group: 2814  
Filed: March 7, 1997                              Examiner: S. RAO  
For: SUBSTRATE PROCESSING APPARATUS WITH LOCAL  
EXHAUST FOR REMOVING CONTAMINANTS

**REPLY UNDER 37 C.F.R. § 1.116**

Assistant Commissioner of Patents  
and Trademarks  
Washington, D.C. 20231

February 13, 2002

Sir:

This is a reply to the Office Action mailed August 13, 2001.

**AMENDMENT**

**IN THE CLAIMS**

Please amend the claims as follows:

10. (Five Times Amended) A substrate processing apparatus comprising:
- a substrate processing chamber for processing a substrate;
  - a load lock chamber;
  - a gas supply for supplying gas into said load lock chamber;